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President. Jaihyung Won
Tokyo Electron Korea Ltd., Korea

Jaihyung Won was born in Seoul, Korea, in 1963. He received the B.E. degree in material science & engineering from the Inha University, Korea, in 1988, and the M. D. and Ph.D. degrees in electrical engineering from the Osaka University, Japan, in 1995 and 1997, respectively. From 1998 to 2000, he joined Physics Department of the Osaka University in Japan and the Auburn University in USA, as a Postdoctoral Research Associate. Since February 2000, he has been worked in Samsung Electronics as a Thin-Film Technology Group Leader until 2011, and as a SVP, Team Leader until 2014 for Thin-Film technology (CVD, ALD, Metal & CMP), Memory Division including overseas operation of Samsung Austin, and Samsung Xian factories. In 2015, he joined Wonik IPS as a Head Executive VP, Semiconductor Division. Since Jun 2017, he has been working as a President of Tokyo Electron Korea Ltd.

His research and development interests include Thin-Film process and equipment engineering (CVD, Metal, CMP) on memory devices, high-volume semiconductor operation of process integration and equipment engineering for yield enhancement and productivity and Wide-Band-Gap semiconductor physics (optical physics). He was the recipient of the Samsung-Group Technical-Achievement Award by chairman Lee, Kun-Hee of Samsung group, in 2004.